Form PTO-1449

#### U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

ATTORNEY DOCKET NO. M122-2416

PRIORITY SERIAL NO. 10/330,881 10/688 439

LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)

APPLICANT: Trung Tri Doan et al.

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| Examiner's<br>Initials |            | Document<br>Number    | Date                | Name                       |                                  | Class                     | Subclass                              |                    | g Date<br>ropriate |
| a                      | _ ^        | 3,990,927             | 11/1976             | Montier                    |                                  | _                         |                                       |                    | _                  |
| 1                      | AB         | 4,474,975             | 10/1984             | Clemons et al.             |                                  | _                         |                                       |                    |                    |
|                        | AC         | 5,156,881             | 10/1992             | Okano et al.               |                                  |                           |                                       |                    |                    |
|                        | 8          | 5,182,221             | 01/1993             | Sato                       |                                  |                           |                                       |                    |                    |
|                        | <b>A</b> E | 5,410,176             | 04/1995             | Liou et al.                |                                  |                           |                                       | -                  |                    |
|                        | AF         | 5,470,798             | 11/1995             | Ouellet                    | ·                                |                           |                                       |                    |                    |
|                        | AG         | 5,719,085             | 02/1998             | Moon et al.                |                                  | 5                         |                                       |                    |                    |
|                        | AH         | 5,741,740             | 04/1998             | Jang et al.                |                                  |                           |                                       |                    |                    |
| V                      | Al         | 5,776,557             | 07/1998             | Okano et al.               |                                  |                           |                                       |                    |                    |
| FOREIGN F              | ATENT      | DOCUMENTS             | · <del>1</del> ···· | <del>-</del>               |                                  | T                         | <u> </u>                              | 1                  | <u>-</u>           |
|                        |            | Document<br>Number    | Date                | Count                      | try                              | Class                     | Subclass                              | Translation<br>Yes | No                 |
| R-                     | ~          | 02277253A             | 11/1990             | Japan (Hayashide et a      | al.)                             |                           |                                       |                    |                    |
|                        | AK         | 146224                | 01/1996             | Japan                      |                                  |                           |                                       |                    |                    |
|                        | AL.        |                       |                     |                            |                                  |                           |                                       |                    |                    |
| OTHER RE               | FEREN      | ICES (including Autho | r, Title, Date, P   | ertinent Pages, Etc.)      |                                  | _                         |                                       |                    |                    |
| ,0                     | AM         | Beekmann e            | al., Sub-micro      | n Gap Fill and In-Situ Pla | narisation using l               | Flowfill ™ T              | echnology                             | , Electroted       | ch 1-7             |
| na                     |            | ULSI Co               | onference, Port     | land, OR (October 1995)    |                                  |                           |                                       |                    |                    |
|                        | AN         | Horie et al., I       | Kinetics and Me     | chanism of the Reaction    | s of O(³P) with Sil              | H₄, CH₃Sil                | H <sub>3</sub> , (CH <sub>3</sub> )₂S | iH₂, and           |                    |
|                        |            | (CH₃)₃S               | iH, 95 J. PHYS.     | Снем 4393-4400 (1991)      | •                                |                           |                                       |                    |                    |
|                        | AO         | Joshi et al., /       | Plasma Deposit      | ed Organosilicon Hydride   | e Network Polyme                 | ers as Vers               | satile Resis                          | sts for Entir      | ely Dry            |
| V                      |            | Mid-De                | ep UV Photolith     | ography, 1925 SPIE 709     | -720 (January 19                 | 93).                      |                                       |                    |                    |
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Form PTO-1449

## U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

ATTY, DOCKET NO. MI22-2416

PRIORITY SERIAL NO. 19/330,881 LO/688 439

LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)

APPLICANT: Trung Tri Doan et al.

PRIORITY FILING DATE December 23, 2002

PRIORITY GROUP ART UNIT 2813

10/16/03

| Examiner's<br>Initials  |          | Document<br>Number                          | Date  | Name                                      | Class      | Subclass    | Filing<br>If Appro |  |  |  |  |  |  |  |  |
|---|----------|---|---|---|------------|-------------|--------------------|--|--|--|--|--|--|--|--|
| Par   | <b>M</b> | 5,786,039                                   | 07/1998   | Brouquet                                  |            |             |                    |  |  |  |  |  |  |  |  |
|   | AB       | 5,801,083                                   | 09/1998   | Yu et al.                                 |            |             |                    |  |  |  |  |  |  |  |  |
|   | AC       | 5,863,827                                   | 01/1999   | Joyner                                    |            |             | -                  |  |  |  |  |  |  |  |  |
|   | 8        | 5,883,006                                   | 03/1999   | lba                                       | <i></i>    |             |                    |  |  |  |  |  |  |  |  |
|   | Æ        | 5,888,880                                   | 03/1999   | Gardner et al.                            | <u> </u>   |             | -                  |  |  |  |  |  |  |  |  |
|   | AF       | 5,895,253                                   | 04/1999   | Akram                                     | J          |             |                    |  |  |  |  |  |  |  |  |
|   | AG       | 5,904,540                                   | 05/1999   | Sheng et al.                              |            |             |                    |  |  |  |  |  |  |  |  |
| N   | AH       | 5,930,645                                   | 07/1999   | Lyons et al.                              |            |             |                    | _  |  |  |  |  |  |  |  |
| V   | N        | 5,943,585                                   | 08/1999   | May et al.                                | _          |             | _                  |  |  |  |  |  |  |  |  |
| OREIGN I  | PATENT   | DOCUMENTS                                   |   |   |            |             |                    |  |  |  |  |  |  |  |  |
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|   | AL.      |   | V   |   |            |             |                    |  |  |  |  |  |  |  |  |
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| OTHER RE  | Ī        | Kiermasz et a                               | al., <i>Planarisation</i>                           | n for Sub-Micron Devices Utilising a New  | Chemistry  | Electrotec  | h 1-2, DUM         | IÇ   |  |  |  |  |  |  |  |
| OTHER RE  | M        |   | Conference, California (February 1995).             |   |            |             |                    |  |  |  |  |  |  |  |  |
| DITHER RE   | <b>~</b> | Confere                                     | nce, California                                     | (February 1995).                          |            |             |                    | lanarization Process Using a Multi-Coating of Spin-on-Glass, V-MIC Conference, pp. 390-396 |  |  |  |  |  |  |  |
| DITHER RE   | AN AN    |   | ·   |   | Glass, V-N | IIC Confere | ence, pp. 39       | 0-396  |  |  |  |  |  |  |  |
| DTHER RE  |          | Kojima et al.,                              | ·   |   | Glass, V-N | IIC Confere | nce, pp. 39        | 0-396  |  |  |  |  |  |  |  |
| DTHER RE  |          | Kojima et al.,                              | Planarization F<br>3-14, 1988).                     |   |            |             |                    | 0-396  |  |  |  |  |  |  |  |
| DE LE CONTRE LE | AN       | Kojima et al.,<br>(June 1:<br>Matsuura et a | Planarization F<br>3-14, 1988).<br>al., A Highly Re | Process Using a Multi-Coating of Spin-on- |            |             |                    | 0-396  |  |  |  |  |  |  |  |

Sheet 3 of 3 ATTY, DOCKET NO. **PRIORITY SERIAL** U.S. DEPARTMENT OF COMMERCE Form PTO-1449 PATENT AND TRADEMARK OFFICE NO.-10/330,881 MI22-2416 LIST OF ART CITED BY APPLICANT APPLICANT: Trung Tri Doan et al. (Use several sheets if necessary) **PRIORITY FILING DATE PRIORITY GROUP** December 23, 2002 ART UNIT 2813 10/16/03 U.S. PATENT DOCUMENTS Subclass Filing Date Name Document Date "Examiner's If Appropriate Initials Number \* 09/1999 Lin et al. 5,950,094 AB 5,960,299 09/1999 Yew et al. AC 10/1999 Liu et al. 5,972,773 AD 12/1999 Bergemont et al. 5,998,280 Æ 6,030,881 02/2000 Papasouliotis et al. 04/2000 Nam 6,051,477 12/2000 Li et al. 6,156,674 10/2001 Doan et al. 6,300,219 B1 FOREIGN PATENT DOCUMENTS Translation Date Country Class Schrings Document Yes AK OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.) Matsuura et al., Novel Self-planarizing CVD Oxide for Interlayer Dielectric Applications, 94 IEEE 117-120 (1994). McClatchie et al. Low Dielectric Constant Flowfill™ Technology for IMD Applications, 7 pages (pre-August AN 1999). Withnall et al., Matrix Reactions of Methylsilanes and Oxygen Atoms, 92 J. Phys. CHEM. 594-602 (1988). AO

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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DATE CONSIDERED

**EXAMINER** 

# Form PTO-1449 QUETO

## U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

ATTY. DOCKET NO. MI22-2416

SERIAL NO. 10/688,439

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APPLICANT: Trung Tri Doan et al.

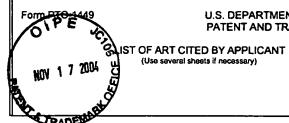
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| DS                      | *  | 5,105,253          | 04/1992 | Pollock       | 357   | 49       |                            |
| i                       | AB | 5,604,149          | 02/1997 | Paoli et al.  | 437   | 67       | 17                         |
|                         | AC | 5,616,513          | 04/1997 | Shepard       | 438   | 402      |                            |
|                         | AD | 5,786,263          | 07/1998 | Perera        | 438   | 431      |                            |
|                         | Æ  | 5,895,255          | 04/1999 | Tsuchiaki     | 438   | 427      |                            |
|                         | AF | 5,923,073          | 07/1999 | Aoki et al.   | 257   | 501      |                            |
|                         | AG | 5,981,354          | 11/1999 | Spikes et al. | 438   | 424      |                            |
|                         | АН | 5,989,978          | 11/1999 | Peidous       | 438   | 436      |                            |
| V                       | AJ | 6,033,961          | 03/2000 | Xu et al.     | 438   | 295      |                            |

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| De        | N     | 05-315441          | 11/1993 | Japan                | 1     |         | Yes | No     |
|           | AK    | 06-334031          | 12/1994 | Japan                |       | 1.      |     |        |
| V         | AL    | 02/27063 A2        | 4/2002  | WIPO (Gordon et al.) |       |         |     |        |

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| 05      | _ ^^  | 4     | Curtis et al, "APCVD TEOS: O3 Advanced Trench Isolation Applications", Semiconductor Fabtech, 9th Ed.,     |
|         |       |       | p. 241 - 247   |
|         | ٨     | '     | George, S.M. et al., "Atomic layer controlled deposition of SiO₂ and Al₂O₃ using ABAB binary reaction      |
|         |       |       | sequence chemistry", Applied Surface Science 82/83, Elsevier Science B.V., July 10, 1994, p. 460-467.      |
|         | _ AC  | )     | Morishita et al. "Atomic-layer chemical-vapor-deposition of silicon-nitride", Applied Surface Science 112, |
|         |       |       | Elsevier Science B.V., 1997, p. 198-204.   |
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(Use several sheets if necessary)

ATTY. DOCKET NO. MI22-2416

SERIAL NO. 10/688,439

APPLICANT: Trung Tri Doan et al.

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| 959                    | *  | 6,090,675          | 07/2000 | Lee et al.      | 438   | 301      |                               |
|                        | AB | 6,171,962          | 01/2001 | Karlsson et al. | 438   | 692      |                               |
|                        | AC | 6,187,651          | 02/2001 | Oh              | 438   | 435      |                               |
|                        | AĐ | 6,191,002          | 02/2001 | Koyanagi        | 438   | 431      |                               |
|                        | Æ  | 6,300,219          | 10/2001 | Doan et al.     | 438   | 424      |                               |
|                        | AF | 6,326,282          | 12/2001 | Park et al.     | 438   | 424      |                               |
|                        | AG | 6,329,266          | 11/2001 | Hwang et al.    | 438   | 424      |                               |
| . /                    | АН | 6,355,966          | 03/2002 | Trivedi         | 257   | 499      |                               |
| V                      | AJ | 6,583,060          | 06/2003 | Trivedi         | 438   | 700      |                               |

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| Da           |         | АМ        | Yokoyama et al. "Atomic layer controlled deposition of silicon nitride and in situ growth observation by infrared |
| <i>\pu</i> > |         |           | reflection absorption spectroscopy", Applied Surface Science 112, Elsevier Science B.V., 1997, p. 75-81.          |
| 1            |         | AN        | Gasser et al., "Quasi-monolayer deposition of silicon dioxide", Elsevier Science S.A., 1994, p. 213-218.          |
|              |         |           |   |
|              |         | <b>AO</b> | Shareef et al., "Subatmospheric chemical vapor deposition ozone/TEOS process for SiO₂ trench filling",            |
| V            |         |           | J. Vac. Sci. Technol. B 13(4), Jul/Aug 1995, p. 1888-1892.  |
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Form PTO-1449

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### U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

ATTY, DOCKET NO. MI22-2416

SERIAL NO. 10/688,439

IST OF ART CITED BY APPLICANT (Use several sheets if necessary)

NT APPLICANT: Trung Tri Doan et al.

FILING DATE October 16, 2003

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U.S. PATENT DOCUMENTS Filing Date If Appropriate "Examiner's Document Date Subclass Name Initials Number 6,448,150 09/2002 Tsai et al. 438 427 AB 09/2003 Kamath et al. 6,617,251 438 691 AC 6,719,012 4/2004 Doan et al. AD 6/2003 6,583,028 Doan et al. ΑE 6,534,395 B1 10/2001 Werkhoven et al. 2001/0006255 A1 07/2001 Kwon et al. 257 751 2001/0006839 A1 07/2001 438 435 АH 2001/0046753 A1 11/2001 Gonzalez et al. 438 424 2002/0004284 A1 01/2002 438 427

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|          | A.      |                            | Ç    | 13724708 | 63    |  |             |    |  |
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| 0.        | AM    | Disclosed Anonymous 32246, "Substrate Contact with Closed Bottom Trenches", Research Disclosure, Feb.              |
| PS        |       | 1991, 1 page.  |
|           | AN    | Hausmann et al., Rapid Vapor Deposition of Highly Conformal Silica Nanolaminates, 298 SCIENCE 402-406              |
|           |       | (October 11, 2002)   |
|           | AO    | Miller et al., Self-limiting chemical vapor deposition of an ultra-thin silicon oxide film using tri-(tert-butoxy) |
|           |       | Silanol, 397 Thin Solid Films 78-82 (2001).  |
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| Dan                     | _ ^      | 10/931,524                        |                      | Sandhu                                |                               |              |               | 08/31/2           | 2004               |
|                         | AB       | 10/615,051                        |                      | Vaartstra                             |                               |              |               | 07/07/2           | 2003               |
|                         | AC       | 10/655,699                        |                      | Derderian et al.                      |                               |              |               | 09/05/2           | 2003               |
| ¥                       | AD       | 10/806,923                        |                      | Li et al.                             |                               |              |               | 03/22/2           | 2004               |
|                         | AE       |                                   |                      |                                       | 1372                          | 47(          | 86            | 3                 |                    |
|                         | AF       |                                   |                      | / E                                   | 1312                          |              |               |                   |                    |
|                         | AG       |                                   |                      |                                       |                               |              |               |                   |                    |
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|                         | AJ       |                                   |                      | /                                     |                               | <u> </u>     | ·             | Yes               | No                 |
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| Ps                      | N        | Hausmann e                        | et al., "Catalytic v | apor deposition of highly             | conformal silica r            | nanolamin    | ates", Depa   | irtment of        |                    |
| //                      |          | Chemistry a                       | nd Chemical Bio      | logy, Harvard University,             | May 14, 2002, pp              | . 1-13.      |               |                   | ·                  |
| p                       | AK       | Klaus et al.,                     | Atomic Layer De      | eposition of SiO₂ Using Co            | atalyzed and Unc              | atalyzed S   | Self-Limiting | Surface           |                    |
|                         |          | Reaction                          | ons, 6 Surface I     | REVIEW AND LETTERS, No.               | s. 3 and 4, pp. 43            | 5-448 (199   | 99).          | <del>,</del>      |                    |
|                         | AL.      | ·                                 | - <u>-</u>           |                                       |                               | _            |               |                   |                    |
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| 13                      |            | 5,770,469   | 06/23/9B                              | Uram et al.                                    |                                | 437         | 240             | <del> </del>       | _               |
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| EXAMINER                | 5/2        | DATE CONSI  | DEREO L                               | 17/05  |                                |             |                 |                    |                 |
| EXAMINER:               | Initial it | reference considered, w<br>copy of this form with nex | hether or not dita<br>t communication | tion is in conformance with N<br>to applicant. | IPEP 609; Draw line            | through cit | ation it not in | conformano         | e and not       |